East & USPAUSPT, WPID Default Plurals Time Stamp Ref Hits Search Query Operator # L1 1265145 pore or porous or foramin\$ or hole US-PGPUB; OR ON 2005/11/09 21:29 **USPAT** L2 mesh\$ US-PGPUB; ON 2005/11/09 21:29 343524 OR **USPAT** L3 ON 1735175 protect\$ or mask\$ or resist or US-PGPUB; OR 2005/11/09 21:29 photoresist or photomask or tape **USPAT** US-PGPUB; ON L4 544567 grind\$ or lap\$ or cmp or \$polish\$ OR 2005/11/09 21:29 or chemimech\$ or abrad\$ **USPAT L**5 2423252 frontside\$ or backside\$ or front or US-PGPUB: OR ON 2005/11/09 21:29 **USPAT US-PGPUB**; L6 2883937 semiconduct\$ or wafer or chip or OR ON 2005/11/09 21:30 device **USPAT L**7 96039 (1 or 2) with 3 US-PGPUB: OR ON 2005/11/09 21:06 USPAT L8 3648 US-PGPUB: OR ON 7 same 4 2005/11/09 21:06 **USPAT** L9 1192 6 same 8 US-PGPUB; OR ON 2005/11/09 21:07 **USPAT US-PGPUB:** ON L10 372103 3 with 6 OR 2005/11/09 21:07 **USPAT** L11 130839 3 with 5 US-PGPUB: OR ON 2005/11/09 21:08 **USPAT** L12 721 **US-PGPUB:** OR ON 9 same (10 or 11) 2005/11/09 21:08 **USPAT** 3 with 5 with 6 US-PGPUB; ON L13 21166 OR 2005/11/09 21:09 USPAT L14 143 **US-PGPUB**: 12 same 13 ON OR 2005/11/09 21:10 **USPAT** L15 1468996 JPO: pore or porous or foramin\$ or hole OR ON 2005/11/09 21:29 DERWENT L16 151792 mesh\$ OR ON JPO; 2005/11/09 21:29 **DERWENT** L17 1377221 protect\$ or mask\$ or resist or ON JPO: OR 2005/11/09 21:29 photoresist or photomask or tape DERWENT L18 330138 grind\$ or lap\$ or cmp or \$polish\$ JPO; OR ON 2005/11/09 21:29 or chemimech\$ or abrad\$ **DERWENT** L19 1519800 ON frontside\$ or backside\$ or front or JPO; OR 2005/11/09 21:29 back DERWENT L20 5656420 semiconduct\$ or wafer or chip or JPO: OR ON 2005/11/09 21:30 device DERWENT L21 59275 (15 or 16) with 17 JPO; OR ON 2005/11/09 21:30 DERWENT

JPO:

DERWENT

ON

OR

2005/11/09 21:55

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L22

18 and (19 or 20) and 21

L23	73243	18 with (19 or 20)	JPO; DERWENT	OR	ON	2005/11/09 21:31
L24	318	22 and 23	JPO; DERWENT	OR	ON	2005/11/09 21:32
L25	296568	17 with (19 or 20)	JPO; DERWENT	OR	ON	2005/11/09 21:32
L26	224	24 and 25	JPO; DERWENT	OR	ON	2005/11/09 21:33
L27	129	24 and 25	DERWENT	OR	ON	2005/11/09 21:51
L28	0	26 not 27	DERWENT	OR	ON	2005/11/09 21:51
L29	52	24 not 27	DERWENT	OR	ON	2005/11/09 21:51
L30	188	22 not 24	DERWENT	OR	ON	2005/11/09 21:56

(FILE 'HOME' ENTERED AT 17:23:36 ON 09 NOV 2005)

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FILE 'CAPLUS' ENTERED AT 17:23:44 ON 09 NOV 2005
        616661 S PORE OR PORES OR HOLE OR HOLES OR POROUS OR OPENINGS
L1
L2
         86685 S MESH?
L3
           3661 S FORAMIN?
         730376 S PROTECT? OR MASK? OR RESIST OR PHOTORESIST OR PHOTOMASK?
L4
         54752 S TAPE OR TAPES
L5
         212935 S GRIND? OR LAP? OR ABRAD? OR CMP OR ?POLISH? OR CHEMIMECH?
L6
            548 S FORAMINOUS
L7
        1120127 S WAFER? OR SEMICONDUCT? OR CHIP? OR DEVICE
L8
L9
        119084 S FRONT?
L10
        482200 S BACK?
         12419 S (L1 OR L2 OR L3) (10A) (L4 OR L5)
L11
L12
         43128 S (L4 OR L5) (10A) L8
            812 S L12(10A)(L9 OR L10)
L13
             50 S L11 AND L13
L14
     FILE 'JAPIO' ENTERED AT 17:28:55 ON 09 NOV 2005
L15
           65 S L14
     FILE 'USPAT2' ENTERED AT 17:29:47 ON 09 NOV 2005
           135 S L11(P)L13
L16
             37 S L16(P)(CUT? OR SLICE? OR CHIPS? OR SEPARATE? OR SCRIBE? OR LA
L17
            72 S L11(15A)L13
L18
L19
            60 S L18 NOT L17
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